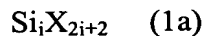


IN THE CLAIMS

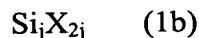
Please amend the claims as follows:

Claim 1 (Original): A silicon-cobalt film forming composition which comprises a silicon compound and a cobalt compound.

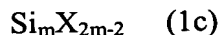
Claim 2 (Original): The composition of claim 1, wherein the silicon compound is at least one compound selected from the group consisting of compounds represented by the following formulae (1a) to (1d):



(wherein X is a hydrogen atom, a halogen atom or a monovalent organic group, and i is an integer of 2 or larger),



(wherein X is a hydrogen atom, a halogen atom or a monovalent organic group, and j is an integer of 3 or larger),



(wherein X is a hydrogen atom, a halogen atom or a monovalent organic group, and m is an integer of 4 or larger),



(wherein X is a hydrogen atom, a halogen atom or a monovalent organic group, and k is 6, 8 or 10).

Claim 3 (Currently Amended): The composition of claim 1 or 2, wherein the cobalt compound is a cobalt complex having at least either one of a CO ligand or a π ligand.

Claim 4 (Currently Amended): A method for forming a silicon-cobalt film which comprises the steps of forming a coating film of the silicon-cobalt film forming composition of ~~any of claims 1 to 3~~ claim 1 on a substrate and subjecting the film to a heat treatment and/or a light treatment.

Claim 5 (Original): A silicon-cobalt film formed by the method of claim 4.